

Notice of References Cited

Application/Control No.

09/234,233

Examiner

DAVID VU

Applicant(s)/Patent Under
Reexamination
LI ET AL.

Art Unit

2818

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U.S. PATENT DOCUMENTS

*		DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	DOCUMENT SOURCE **	
							APS	OTHER
<input type="checkbox"/>	A	5,962,581	Oct. 1999	Hayase et al.	524	588	<input type="checkbox"/>	<input type="checkbox"/>
<input type="checkbox"/>	B						<input type="checkbox"/>	<input type="checkbox"/>
<input type="checkbox"/>	C						<input type="checkbox"/>	<input type="checkbox"/>
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FOREIGN PATENT DOCUMENTS

*		DOCUMENT NO.	DATE	COUNTRY	NAME	CLASS	SUBCLASS	DOCUMENT SOURCE **	
								APS	OTHER
<input type="checkbox"/>	N	EP 0942330A1	Sep. 1999	Europe	Joubert et al.	G03F	7/095	<input type="checkbox"/>	<input type="checkbox"/>
<input type="checkbox"/>	O							<input type="checkbox"/>	<input type="checkbox"/>
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<input type="checkbox"/>	T							<input type="checkbox"/>	<input type="checkbox"/>

NON-PATENT DOCUMENTS

*		DOCUMENT (Including Author, Title Date, Source, and Pertinent Pages)	DOCUMENT SOURCE **	
			APS	OTHER
<input type="checkbox"/>	U	Timothy W. Weidman, et al., New Photodefinable glass etch masks for entirely dry photolithography: Plasma deposited organosilicon hydride polymers (Applied Physics Letters, vol.62, no.4, January 25, 1993, pgs.372-374)	<input type="checkbox"/>	<input type="checkbox"/>
<input checked="" type="checkbox"/>	V	Weidman, et al., All dry lithography: Applications of plasma polymerized methylsilane as a single layer resist and silicon dioxide precursor (Journal of Photopolymer Science and Technology, vol.8, no.8, 1995, pgs.679-686)	<input type="checkbox"/>	<input type="checkbox"/>
<input type="checkbox"/>	W	Joubert O et al., Application of Plasma Polymerized Methylsilane in an all dry resist process for 193 and 248 nm lithography (Microelectronic Engineering, vol.30, no.1/04, 1 January 1996, pages 275-278)	<input type="checkbox"/>	<input type="checkbox"/>
<input type="checkbox"/>	X		<input type="checkbox"/>	<input type="checkbox"/>

*A copy of this reference is not being furnished with this Office action. (See Manual of Patent Examining Procedure, Section 707.05(a).)

**APS encompasses any electronic search i.e. text, image, and Commercial Databases.

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